

APPENDIX I

FAA No Hazard Determination



Federal Aviation Administration
Air Traffic Airspace Branch, ASW-520
2601 Meacham Blvd.
Fort Worth, TX 76137-0520

Aeronautical Study No.
2008-AEA-1215-OE

Issued Date: 03/19/2008

Steve Groseclose, Esq.
Advanced Micro Devices, Inc.
5204 E. Ben White Blvd.
MS 600 1A
Austin, TX 78741

***** DETERMINATION OF NO HAZARD TO AIR NAVIGATION *****

The Federal Aviation Administration has conducted an aeronautical study under the provisions of 49 U.S.C., Section 44718 and if applicable Title 14 of the Code of Federal Regulations, part 77, concerning:

Structure:	Building AMD - Fab 4X
Location:	Saratoga Springs, NY
Latitude:	42-58-00.83N NAD 83
Longitude:	73-45-13.09W
Heights:	110 feet above ground level (AGL) 450 feet above mean sea level (AMSL)

This aeronautical study revealed that the structure does not exceed obstruction standards and would not be a hazard to air navigation provided the following condition(s), if any, is(are) met:

Based on this evaluation, marking and lighting are not necessary for aviation safety. However, if marking and/or lighting are accomplished on a voluntary basis, we recommend it be installed and maintained in accordance with FAA Advisory circular 70/7460-1 K Change 2.

This determination is based, in part, on the foregoing description which includes specific coordinates, heights, frequency(ies) and power. Any changes in coordinates, heights, and frequencies or use of greater power will void this determination. Any future construction or alteration, including increase to heights, power, or the addition of other transmitters, requires separate notice to the FAA.

This determination does include temporary construction equipment such as cranes, derricks, etc., which may be used during actual construction of the structure. However, this equipment shall not exceed the overall heights as indicated above. Equipment which has a height greater than the studied structure requires separate notice to the FAA.

This determination concerns the effect of this structure on the safe and efficient use of navigable airspace by aircraft and does not relieve the sponsor of compliance responsibilities relating to any law, ordinance, or regulation of any Federal, State, or local government body.

A copy of this determination will be forwarded to the Federal Communications Commission if the structure is subject to their licensing authority.

If we can be of further assistance, please contact our office at (718) 553-4542. On any future correspondence concerning this matter, please refer to Aeronautical Study Number 2008-AEA-1215-OE.

Signature Control No: 565550-101866720
Katie Venticinque
Technician

(DNE)

Notice of Proposed Construction or Alteration - Off Airport

Project Name: ADVAN-000089341-08 **Sponsor:** Advanced Micro Devices, Inc.

Details for Case : AMD - Fab 4X

Show Project Summary

Case Status		Date Accepted: 03/11/2008	
ASN: 2008-AEA-1215-OE		Date Determined:	
Status: Accepted		Letters: None	
Construction / Alteration Information		Structure Summary	
Notice Of: Construction		Structure Type: Building	
Duration: Permanent		Structure Name: AMD - Fab 4X	
<i>if Temporary :</i> Months: Days:		FCC Number:	
Work Schedule - Start: 08/17/2008		Prior ASN:	
Work Schedule - End: 12/31/2009			
State Filing: Not filed with State			
Structure Details		Common Frequency Bands	
Latitude: 42° 58' 0.83" N		Low Freq	High Freq Freq Unit ERP ERP Unit
Longitude: 73° 45' 13.09" W		Specific Frequencies	
Horizontal Datum: NAD83			
Site Elevation (SE): 340 (nearest foot)			
Structure Height (AGL): 110 (nearest foot)			
Marking/Lighting: None			
<i>Other :</i>			
Nearest City: Saratoga Springs			
Nearest State: New York			
Description of Location:	Luther Forest Technology Campus, Malta, New York. See site location on attached USGS map.		
Description of Proposal:	Construction of semiconductor manufacturing facility, consisting of four main buildings and various service buildings. Total footprint of all buildings approximately 890,000 square feet. See attachments, including area maps and building cross-sections.		

